

Supporting information

P-doped in situ induced Se vacancy enhances the supercapacitor performance of NiCo₂Se₄

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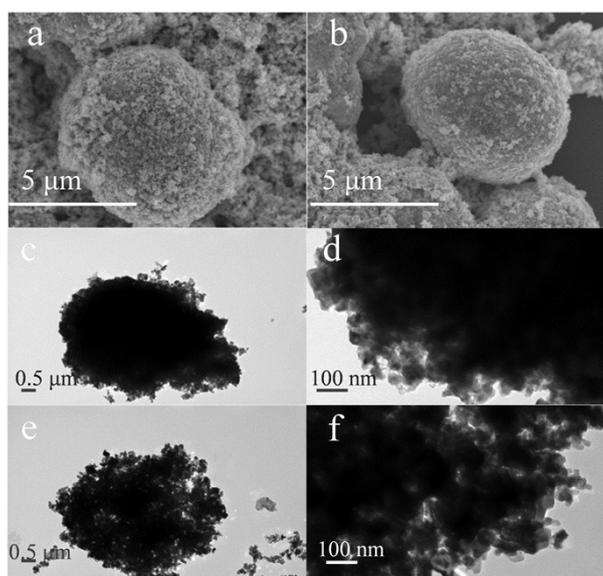


Fig. S1 (a) SEM images of $\text{NiCo}_2\text{Se}_x\text{-P}_{0.5}$, (b) SEM images of $\text{NiCo}_2\text{Se}_x\text{-P}_2$, (c-d) TEM images of $\text{NiCo}_2\text{Se}_x\text{-P}_{0.5}$, (e-f) TEM images of $\text{NiCo}_2\text{Se}_x\text{-P}_2$.

SEM images of $\text{NiCo}_2\text{Se}_x\text{-P}_{0.5}$ and $\text{NiCo}_2\text{Se}_x\text{-P}_2$ are shown in Fig. S1(a-b). After the phosphating treatment, both $\text{NiCo}_2\text{Se}_x\text{-P}_{0.5}$ and $\text{NiCo}_2\text{Se}_x\text{-P}_2$ showed a microsphere morphology with an average size of $5\ \mu\text{m}$, and the spherical surface was covered with a large number of nanoparticles. The low-magnification TEM images of $\text{NiCo}_2\text{Se}_x\text{-P}_{0.5}$ and $\text{NiCo}_2\text{Se}_x\text{-P}_2$ are shown in Fig. S1(c-f), and their size is about $5\ \mu\text{m}$, which is in agreement with the SEM results. Compared with $\text{NiCo}_2\text{Se}_x\text{-P}_1$ material, they are all microspheres, but further observation can be found that the surface of $\text{NiCo}_2\text{Se}_x\text{-P}_1$ material is needle-like, which may be that the amount of phosphorus doping will have some effect on its morphology, resulting in differences in the surface structure of the material. As for $\text{NiCo}_2\text{Se}_x\text{-P}_1$, the mesh structure formed by interconnecting neighboring nano-needles on its surface has abundant pores, and this multi-channel structure can accelerate the rapid penetration of electrolyte ions in the active material. Therefore, the electrochemical performance of $\text{NiCo}_2\text{Se}_x\text{-P}_1$ obtained after phosphorization treatment are better than the other two samples. Based on this we consider $\text{NiCo}_2\text{Se}_x\text{-P}_1$ as a typical sample for research.

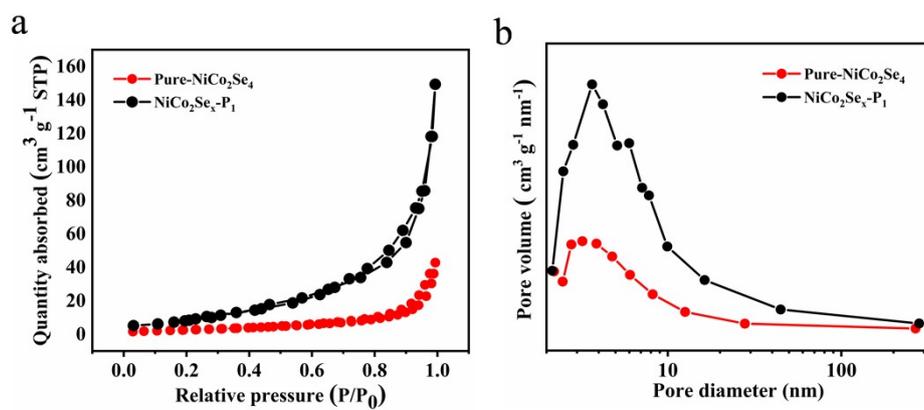


Fig. S2 (a) N₂ adsorption/desorption isotherm, (b) Pore size distribution.

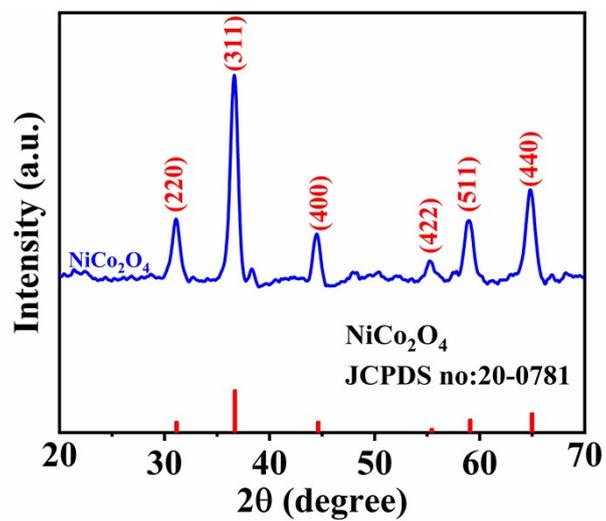


Fig. S3 XRD pattern of NiCo precursor.

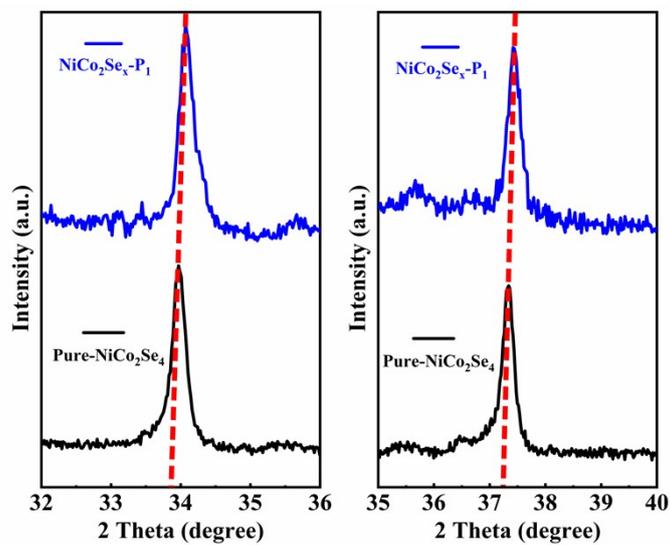


Fig. S4 XRD comparison of (210) and (211) crystal planes of Pure- NiCo_2Se_4 and $\text{NiCo}_2\text{Se}_x\text{-P}_1$.

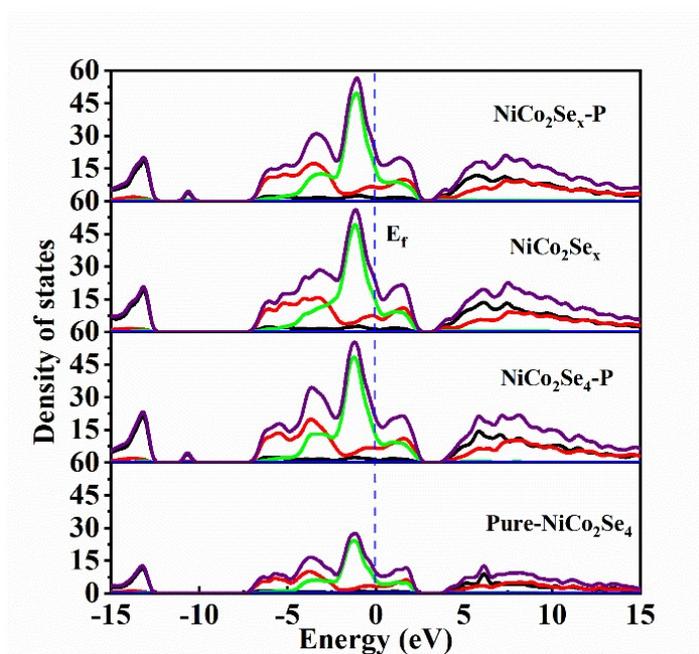


Fig. S5 DOS diagrams of Pure- NiCo_2Se_4 , $\text{NiCo}_2\text{Se}_4\text{-P}$, NiCo_2Se_x and $\text{NiCo}_2\text{Se}_x\text{-P}$.

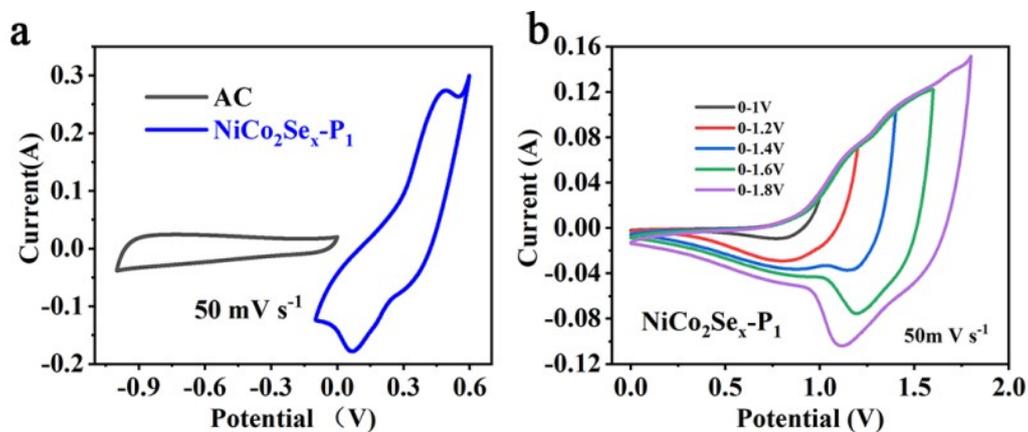


Fig. S6 (a) Comparison of CV curves of AC electrode and NiCo₂Se_x-P₁ electrode at 50 mV s⁻¹ scan rate, (b) CV curves of different voltage windows at NiCo₂Se_x-P₁//AC scan rate of 50 mV s⁻¹.

Table. S1 Performance comparison of NiCo₂Se_x-P₁//AC devices with recently reported hybrid supercapacitors

Supercapacitor device	energy density (Wh kg ⁻¹)	power density (W kg ⁻¹)	Reference
CoNi ₂ S ₄ //Bi ₂ O ₃	86.6	1600	1
Ni ₂ Co ₄ Se ₄ //HPC	34.8	399.9	2
NiCo ₂ Se ₄ /rGO//TRGO	37.83	1433.55	3
(Ni _{0.33} Co _{0.67})Se ₂ CHSs//AC	29.1	800	4
NiCo ₂ Se ₄ //AC	25	490	5
Ni _{0.67} Co _{0.33} Se//RGO	36.7	750	6
(Ni _{0.5} Co _{0.5}) _{0.85} Se//carbon	70.58	320.02	7
NiCo₂Se_x-P₁//AC	94.61	799.92	This work

References

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